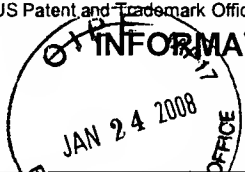


FORM PTO-1449 (Modified)		US DEPARTMENT OF COMMERCE		Docket No. 050623.61	Application No. 09/997,450
US Patent and Trademark Office		INFORMATION DISCLOSURE CITATION in an Application (Use several sheets if necessary)			
					
		Applicant Shamim Malik et al.		Filing Date November 30, 2001	Group Art Unit 3731

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/Ryan Severson/				06/27/2008				
EXAMINER: Initial if references considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.								